

<b>Notice of References Cited</b>		Application/Control No. 09/776,329	Applicant(s)/Patent Under Reexamination SEUTTER ET AL.	
		Examiner Toniae M. Thomas	Art Unit 2822	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2002/0094632 A1	07-2002	Agarwal et al.	438/239
	B	US-6,001,415 B1	12-1999	Nogami et al.	427/97
	C	US-6,428,859 B1	08-2002	Chiang et al.	427/457
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Ritala, M. et al., "Controlled TaN, Ta <sub>3</sub> N <sub>5</sub> , and TaO <sub>x</sub> N <sub>y</sub> Thin Films by Atomic Layer Deposition," Chem. Mater., 1999, Vol. 11, pp. 1712-1718.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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